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STMicroelectronics

ROUTE60™: a new vertical probing technology



June 3-6, 2007 San Diego, CA USA

Authors

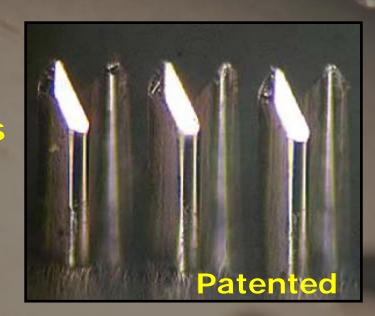
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Technology Introduction - Needles

- Buckling Beam style: higher possibility to control the gram force
- Needle section equivalent to 3 mils Ø wire:
 - Robust mechanics
 - High current capability
- Flattened section of needles allows fine Pitch applications down to 60μm



Technology Introduction - Design

- Gram Force adjustable between 5 to 8 g
- Small scrub action proportional to OD
- Tight Alignment: ±10 μm
- Planarity range : 40 μm
- Hard Ceramic:
 - CTE 3.3 ppm/°C close to Silicon
 - Low needles friction
- Needles Assembly: no template required, easy tip replacement

Qualification on a 80µm pitch product

- Embedded Flash Microcontroller for automotive market
- Small pad opening (65μm × 70μm)
- Up to 4 EWS Tests, 3 testing temps KGD flow
- Small probing process margins with present Epoxy probe cards mainly @ HOT temp:
 - Passivation breakage
 - Large scrub marks impacted area
- Benchmark with Epoxy probe cards

Product test flow description

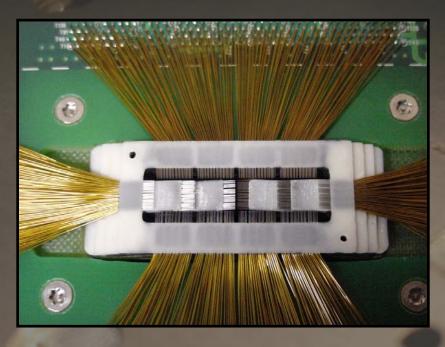
Package Flow:

- EWST1 @ Room T -Vertical //32
- Bake (24 h)
- EWST2 @ Room T -Vertical //32
- EWST3 @ Room T -Epoxy //4

KGD Flow:

- EWST1 @ Room T -Vertical //32
- Bake (24 h)
- EWST2 @ + 125°C Vertical //16
- EWST3 @ + 125°C -Epoxy //4
- EWST4 @ 40°C -Epoxy //4

Probe Cards Pictures

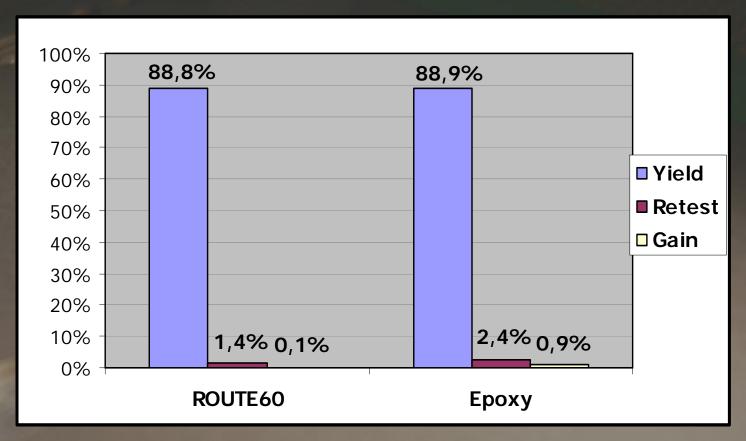




Epoxy

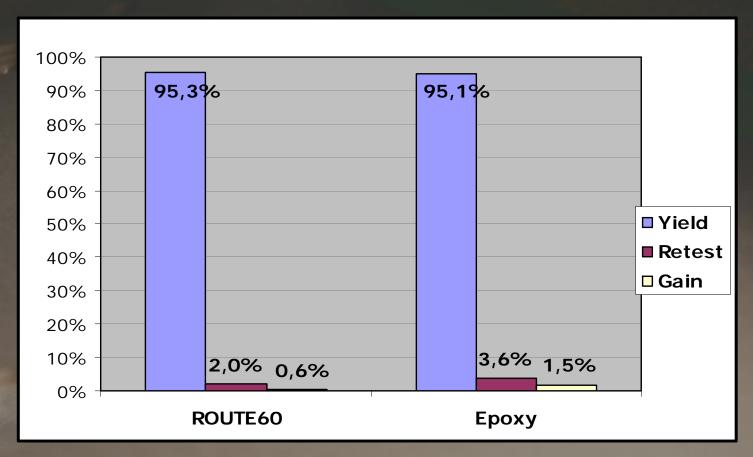
Vertical ROUTE60™

Electrical results @ ROOM T (EWS3)



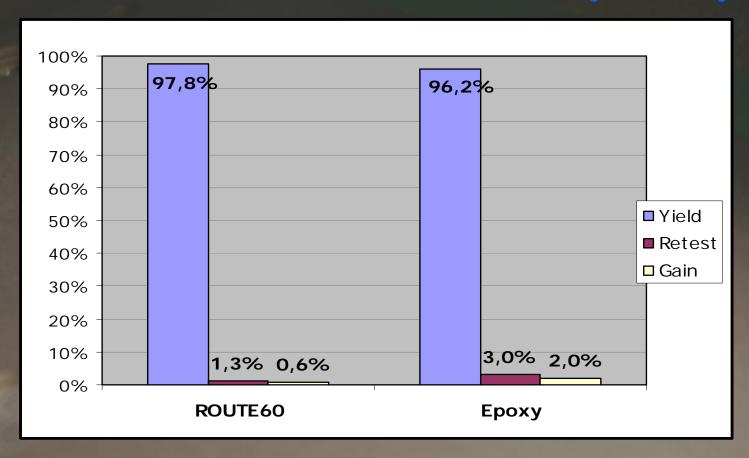
- ♦ Retest rate: 1.0%
- ◆ Gain rate: 0.8%

Electrical results @ +125°C (EWS3)



- ◆ Retest rate: 1.6%
- ◆ Gain rate: 0.9%

Electrical results @ -40°C (EWS4)



◆ Retest rate: - 1.7%

◆ Gain rate: - 1.4%

Mechanical Results @ +125°C: ROUTE60™

1/4		CENTER		SCRUB		VITRIF	
		X	Υ	L	W	L	W
	UL	N/A	N/A	32,5	32,5	N/A	N/A
	LL	N/A	N/A	10	10	2	2
TIME 0	AVE	33,0	36,0	13,7	14,5	29,4	26
	STDEV	4,6	2,5	1,5	1,1	2,8	3,5
	C _P	N/A	N/A	2,5	3,4	N/A	N/A
	C _{PK}	N/A	N/A	N/A	N/A	3,3	2,3
AGEING	AVE	32	34,3	13,8	14,1	27,6	24,9
	STDEV	3,2	2,4	1,6	1,5	2,8	3,4
	C _P	N/A	N/A	2,3	2,5	N/A	N/A
	C _{PK}	N/A	N/A	N/A	N/A	3,0	2,2

Scrub mark pictures @ +125°C

Epoxy



ROUTE60™

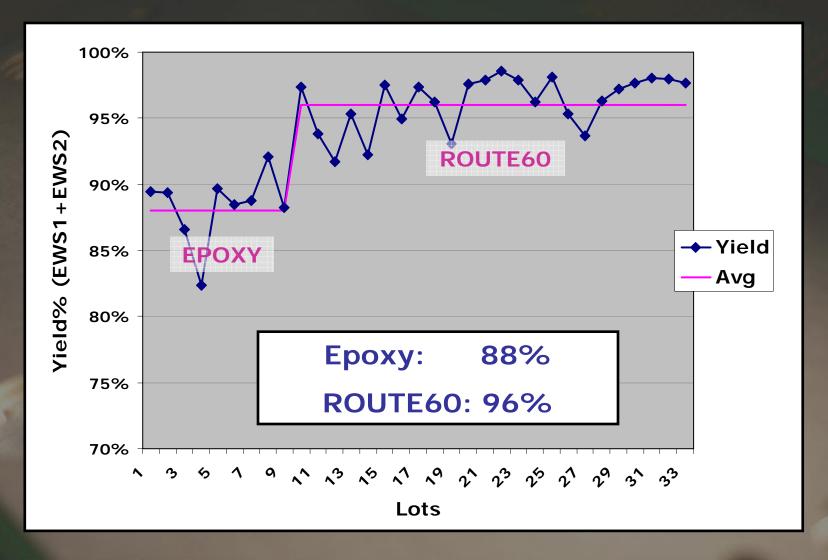


PAD DAMAGE is largely reduced using vertical probe cards: more than 50% of reduction

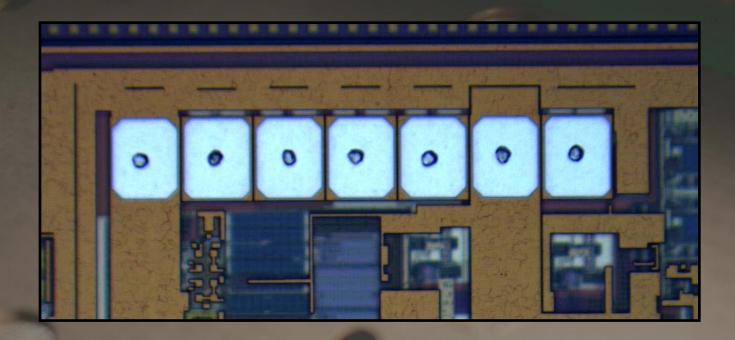
65μm Pitch Product Vehicle Results

- Small pad opening (58μm × 71μm)
- Up to 2 EWS Tests, ROOM T, //8
- Small probing process margins with Epoxy probe cards :
 - Passivation breakage
 - Large scrub marks impacted area
 - Contact issues
- Benchmark with Epoxy probe cards

Electrical results after EWS1 and EWS2



Scrub mark pictures

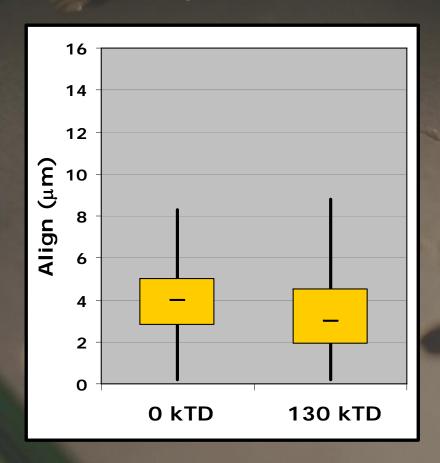


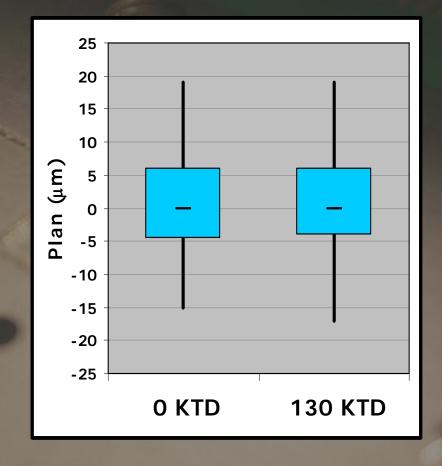
ROUTE60™ on 58×65 μm pads at 65 μm pitch

Mechanical Results

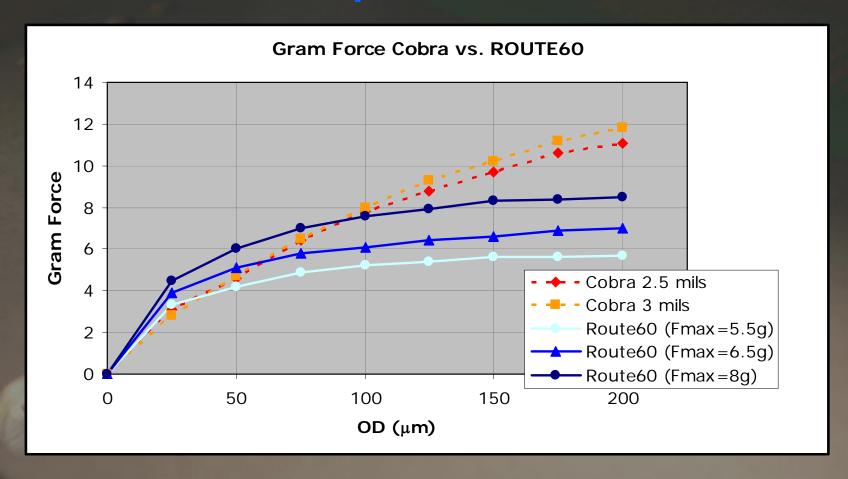
Alignment:

Planarity:



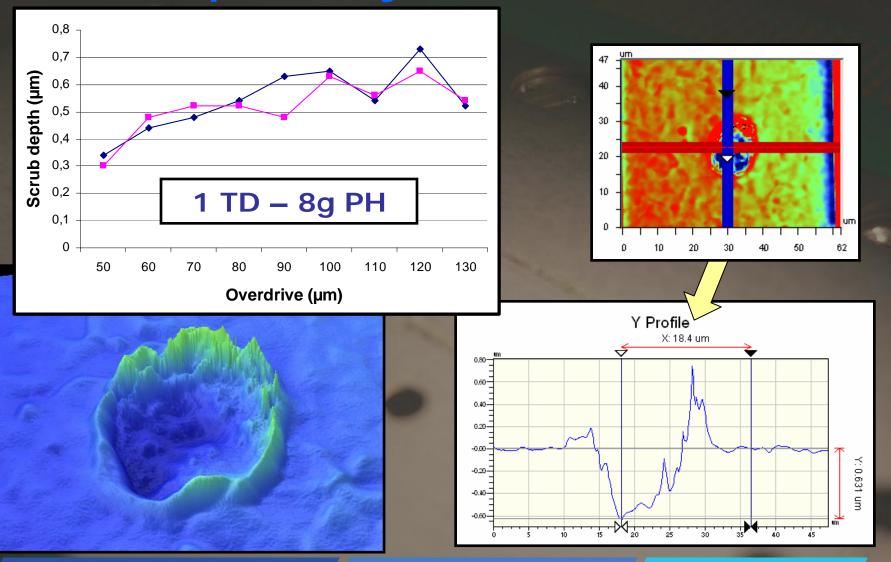


Evaluations on pads over active areas



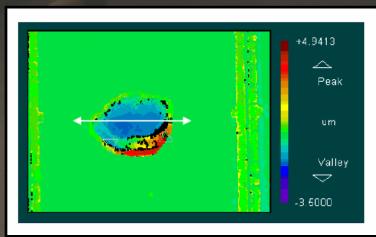
Gram Force adjustable between 5 to 8 g

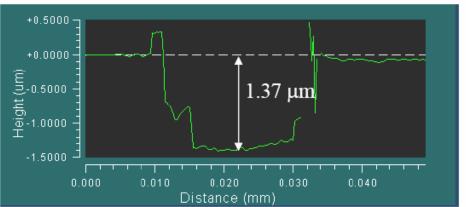
Scrub depth analysis @ ROOM T - 1TD



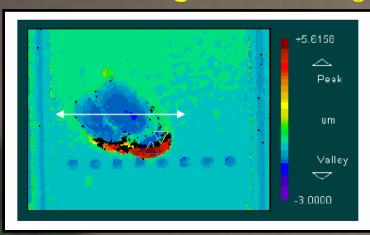
Scrub depth analysis @ +125°C - 9 TDs

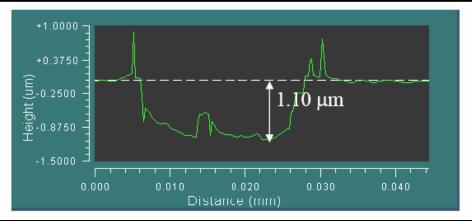
6.5 g PH – Average scrub depth: 1.30 μm



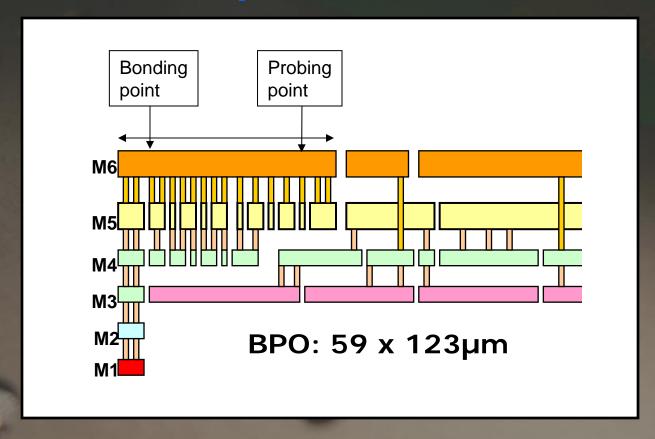


5 g PH – Average scrub depth : 1.15 μm



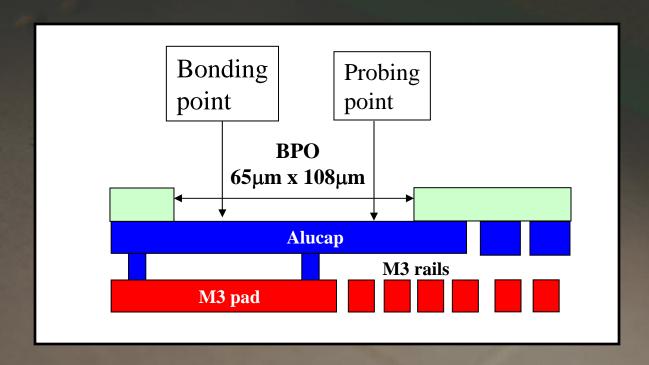


6M2T pad over active



No cracks observed till 125 μm X 6 TDs @ ROOM T with both 8g and 6.5g probe heads

3MOT pad over active area



No cracks observed with 8 g probe head till:

- ◆ 100 μm OD × 9 TDs (6 @ ROOM T + 3 @ +150°C)
- \diamond 125 µm OD × 6 TDs (4 @ ROOM T + 2 @ +150°C)

Conclusions

- ROUTE60™ is the first vertical probing technology successfully released to production in ST, down to 65 μm pitch
- The benchmark with Epoxy probe cards showed:
 - Better electrical contact
 - Lower pad area damage
 - The possibility to probe on active areas playing on the gram force
- This technology seems very promising to probe at 60 μm pitch and on low-k dielectrics

Follow-on work

1. Probing:

- Automotive products, with up to 3 EWS Test
 and up to + 125°C / + 150°C
- Copper metals and Low-k dielectrics
- Probing area down to 50 x 50 μm
- 2. Evaluations at lower pitch, down to 60µm:
 - Life test in progress on test cards at +125 °C
- 3. On-line cleaning optimization

Acknowledgements

A special thanks to:

- ST Castelletto EWS Engineering Team
- ST Rousset EWS Engineering Team
- ST FTM EWS Europe Organization
- ST FTM R&D Agrate
- ST Automotive Product Group
- ST Corporate Package Automation